



**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re the Application of: **Koji NOZAKI et al.**

Group Art Unit: **1752**

Application Number: **10/623,679**

Examiner: **Amanda C. Walke**

Filed: **July 22, 2003**

Confirmation Number: **5083**

For: **RESIST PATTERN THICKENING MATERIAL, RESIST  
PATTERN AND PROCESS FOR FORMING THE SAME, AND  
SEMICONDUCTOR DEVICE AND PROCESS FOR  
MANUFACTURING THE SAME**

Attorney Docket Number: **030891**

Customer Number: **38834**

**RESPONSE**

Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

February 22, 2008

Sir:

This paper is filed in response to the Office Action dated October 2, 2007, the response due date extended to March 2, 2008 by a two-months Extension of Time.

**Remarks** begin on page 2 of this paper.